Subject Name Solutions

4361102 – Winter 2024

Semester 1 Study Material

Detailed Solutions and Explanations

Question 1(a) [3 marks]

Write advantages of High K FINFET.

Solution

Advantage	Description
Reduced leakage current	Better gate control reduces power consumption
Improved performance	Higher drive current and faster switching
Better scalability	Enables continued Moore's law scaling

- **High K dielectric**: Reduces gate leakage significantly
- **3D structure**: Better electrostatic control over channel
- **Lower power**: Reduced static and dynamic power consumption

Mnemonic

"High Performance, Low Power, Better Control"

Question 1(b) [4 marks]

Define terms: (1) pinch off point (2) Threshold Voltage.

Solution

Table 1: Key MOSFET Parameters

Term	Definition	Significance
Pinch-off Point	Point where channel becomes completely depleted	Marks transition to saturation region
Threshold Voltage	Minimum VGS needed to form conducting channel	Determines ON/OFF switching point

- **Pinch-off point**: VDS = VGS - VT, channel narrows to zero width
- **Threshold voltage**: Typically 0.7V for enhancement MOSFET
- **Critical parameters**: Both determine MOSFET operating regions

Mnemonic

"Threshold Turns ON, Pinch-off Points to Saturation"

Question 1(c) [7 marks]

Draw and explain structure of MOSFET transistor.

Solution

Diagram:

```
    Gate (G)
      |

     SiO2

  n+   n+     Source (S) and Drain (D)
     p        P{-substrate  }

    Body (B)
```

Structure Components Table:

Component	Material	Function
Gate	Polysilicon/Metal	Controls channel formation
Gate oxide	SiO2	Insulates gate from substrate
Source/Drain	n+ doped silicon	Current entry/exit points
Substrate	p-type silicon	Provides body connection

- **Channel formation**: Occurs at oxide-semiconductor interface
- **Enhancement mode**: Channel forms when VGS > VT
- **Four-terminal device**: Gate, Source, Drain, Body connections

Mnemonic

"Gate Controls, Oxide Isolates, Source-Drain Conducts"

Question 1(c OR) [7 marks]

Compare Full Voltage Scaling and Constant Voltage Scaling.

Solution

Comparison Table:

Parameter	Full Voltage Scaling	Constant Voltage Scaling
Supply voltage	Scaled down by	Remains constant
Gate oxide thickness	Scaled down by	Scaled down by
Channel length	Scaled down by	Scaled down by
Power density	Remains constant	Increases by ^{2}
Performance	Moderate improvement	Better performance
Reliability	Better	Degraded due to high fields

- **Full scaling**: All dimensions and voltages scaled proportionally
- **Constant voltage**: Only physical dimensions scaled, voltage unchanged
- **Trade-off**: Performance vs power vs reliability

Mnemonic

"Full scales All, Constant keeps Voltage"

Question 2(a) [3 marks]

Draw Resistive Load Inverter. Write the input voltage range for different operating region of operation.

Solution

Circuit Diagram:

```
VDD     RL

         Vout

Vin    M1 (NMOS)

     GND
```

Operating Regions Table:

Region	Input Voltage Range	Output State
Cut-off	Vin < VT	Vout = VDD
Triode	VT < Vin < VDD-VT	Transition
Saturation	Vin > VDD-VT	Vout $\approx 0V$

Mnemonic

"Cut-off High, Triode Transition, Saturation Low"

Question 2(b) [4 marks]

Draw and Explain VDS-ID and VGS-ID characteristics of N channel MOSFET.

Solution

VDS-ID Characteristics:

```
ID ↑
        VGS3
         VGS2
         VGS1
         (VGS3{VGS2VGS1VT)}

          VDS
   Triode  Saturation
```

Characteristics Table:

Characteristic	Region	Behavior
VDS-ID	Triode	Linear increase with VDS
VDS-ID	Saturation	Constant ID (square law)
VGS-ID	Sub-threshold	Exponential increase
VGS-ID	Above VT	Square law relationship

- **Triode region**: ID increases linearly with VDS
- **Saturation**: ID independent of VDS, depends on VGS
- **Square law**: ID (VGS-VT)$^2 insaturation$

Mnemonic

"Linear in Triode, Square in Saturation"

Question 2(c) [7 marks]

Draw & Explain working of Depletion Load NMOS Inverter circuit.

Solution

Circuit Diagram:

```
VDD      ML (Depletion)
           Gate connected to Source
          Vout

Vin       M1 (Enhancement)

      GND
```

Operation Table:

Input	M1 State	ML State	Output
Low (0V)	Cut-off	Active load	High (VDD)
High (VDD)	Saturated	Linear	Low

- **Depletion load**: Always conducting, acts as current source
- **Better performance**: Higher output voltage swing than resistive load
- **Gate connection**: ML gate tied to source for depletion operation
- **Improved noise margin**: Better VOH compared to enhancement load

Mnemonic

"Depletion Always ON, Enhancement Controls Flow"

Question 2(a OR) [3 marks]

Describe advantages of CMOS Inverter.

Solution

Advantages Table:

Advantage	Benefit
Zero static power	No current in steady state
Full voltage swing	Output swings from 0V to VDD
High noise margins	Better noise immunity

- **Complementary operation**: One transistor always OFF
- **High input impedance**: Gate isolation provides high impedance
- **Fast switching**: Low parasitic capacitances

Mnemonic

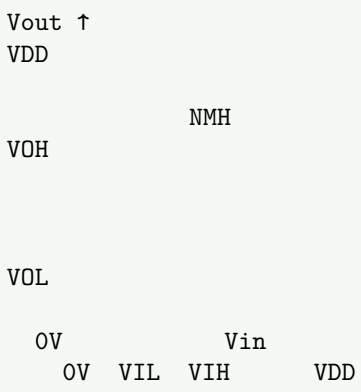
"Zero Power, Full Swing, High Immunity"

Question 2(b OR) [4 marks]

Draw and Explain Noise Margin in detail.

Solution

Voltage Transfer Characteristics:



Noise Margin Parameters:

Parameter	Formula	Typical Value
NMH	VOH - VIH	40% of VDD
NML	VIL - VOL	40% of VDD

- **High noise margin**: Immunity to positive noise
- **Low noise margin**: Immunity to negative noise
- **Better CMOS**: Higher noise margins than other logic families

Mnemonic

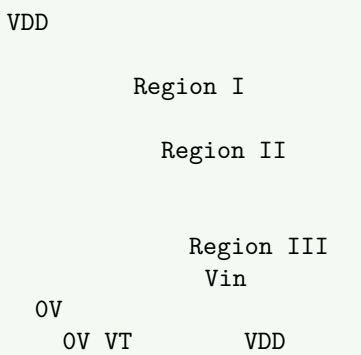
"High goes Higher, Low goes Lower"

Question 2(c OR) [7 marks]

Draw and Explain VTC of N MOS Inverter.

Solution

Voltage Transfer Characteristics:



Operating Regions Table:

Region	Vin Range	M1 State	Vout
I	0 to VT	Cut-off	VDD
II	VT to VT+VTL	Saturation	Decreasing
III	VT+VTL to VDD	Triode	Low

- **Region I**: M1 OFF, no current flow, Vout = VDD
- **Region II**: M1 in saturation, sharp transition
- **Region III**: M1 in triode, gradual decrease
- **Load line**: Determines operating point intersection

Mnemonic

"Cut-off High, Saturation Sharp, Triode Low"

Question 3(a) [3 marks]

Draw and explain generalized multiple input NOR gate structure with Depletion NMOS load.

Solution

Circuit Diagram:

```
VDD      ML (Depletion Load)

           Y = (A+B+C){}

A       M1

B       M2    Parallel Connection

C       M3

      GND
```

Truth Table:

Inputs	Any Input High?	Output Y
All Low	No	High (1)
Any High	Yes	Low (0)

- **Parallel NMOS**: Any input HIGH pulls output LOW
- **NOR operation**: Y = (A+B+C)'
- **Depletion load**: Provides pull-up current

Mnemonic

"Parallel Pulls Down, Depletion Pulls Up"

Question 3(b) [4 marks]

Differentiate AOI and OAI logic circuits.

Solution

Comparison Table:

Parameter	AOI (AND-OR-Invert)	OAI (OR-AND-Invert)
Logic function	Y = (AB + CD)'	Y = ((A+B)(C+D))'
NMOS structure	Series-parallel	Parallel-series
PMOS structure	Parallel-series	Series-parallel
Complexity	Moderate	Moderate

- **AOI**: AND terms ORed then inverted
- **OAI**: OR terms ANDed then inverted

- **CMOS implementation**: Dual network structure
- **Applications**: Complex logic functions in single stage

Mnemonic

"AOI: AND-OR-Invert, OAI: OR-AND-Invert"

Question 3(c) [7 marks]

Implement two input EX-OR gate using CMOS, and logic function Z = (AB +CD)' using NMOS Load.

Solution

EX-OR CMOS Implementation:

```
VDD    pMOS network
        (A{B + AB)}
        Y = A

        nMOS network
        (AB + A{B)}
    GND
```

Z = (AB + CD)' NMOS Implementation:

```
VDD    Resistive Load

        Z = (AB + CD){}

A     M1    B    M2   (Series: AB)

C    M3    D    M4      (Series: CD)

  GND              (Parallel connection)
```

Logic Implementation Table:

Circuit	Function	Implementation
EX-OR	A	Complementary CMOS
AOI	(AB+CD)'	Series-parallel NMOS

- **EX-OR**: Requires transmission gates for efficient implementation
- **AOI function**: Natural NMOS implementation
- **Power consideration**: CMOS has zero static power

Mnemonic

"EX-OR needs Transmission, AOI uses Series-Parallel"

Question 3(a OR) [3 marks]

Draw and explain generalized multiple input NAND gate structure with Depletion NMOS load.

Solution

Circuit Diagram:

```
VDD      ML (Depletion Load)

          Y = (ABC){}

A      M1

B      M2    Series Connection

C      M3

      GND
```

Operation Table:

Condition	Path to Ground	Output Y
All inputs HIGH	Complete path	Low (0)
Any input LOW	Broken path	High (1)

- **Series NMOS**: All inputs must be HIGH to pull output LOW
- **NAND operation**: Y = (ABC)'
- **Depletion load**: Always provides pull-up current

Mnemonic

"Series Needs All, NAND Says Not-AND"

Question 3(b OR) [4 marks]

Implement logic function Y = ((P+R)(S+T))' using CMOS logic.

Solution

CMOS Implementation:

```
VDD    pMOS Network
        P   R in series with S   T in series
        Y = ((P+R)(S+T)){}

        nMOS Network
         (P,R parallel) in series with (S,T parallel)
    GND
```

Truth Table Implementation:

PMOS Network	NMOS Network	Operation
(P+R)'+(S+T)'	**(P+R)(S+T)**	Complementary
P'R' + S'T'	**PS + PT + RS + RT**	De Morgan's law

- **PMOS**: Parallel within groups, series between groups
- **NMOS**: Series within groups, parallel between groups
- **Dual network**: Ensures complementary operation

Mnemonic

"PMOS does Opposite of NMOS"

Question 3(c OR) [7 marks]

Describe the working of SR latch circuit.

Solution

SR Latch Circuit:

```
S    NOR       Q
      G1

     NOR
R     G2       Q{}
```

Truth Table:

S	R	Q(n+1)	Q'(n+1)	State
0	**0**	Q(n)	Q'(n)	Hold
0	**1**	0	1	Reset
1	**0**	1	0	Set
1	**1**	0	0	Invalid

- **Set operation**: S=1, R=0 makes Q=1
- **Reset operation**: S=0, R=1 makes Q=0

- **Hold state**: S=0, R=0 maintains previous state
- **Invalid state**: S=1, R=1 should be avoided
- **Cross-coupled**: Output of one gate feeds input of other

Mnemonic

"Set Sets, Reset Resets, Both Bad"

Question 4(a) [3 marks]

Compare Etching methods in chip fabrication.

Solution

Etching Methods Comparison:

Method	Type	Advantages	Disadvantages
Wet Etching	Chemical	High selectivity, simple	Isotropic, undercut
Dry Etching	Physical/Chemical	Anisotropic, precise	Complex equipment
Plasma Etching	Ion bombardment	Directional control	Damage to surface

- **Wet etching**: Uses liquid chemicals, attacks all directions
- **Dry etching**: Uses gases/plasma, better directional control

- **Selectivity**: Ability to etch one material over another

Mnemonic

"Wet is Wide, Dry is Directional"

Question 4(b) [4 marks]

Write short note on Lithography.

Solution

Lithography Process Steps:

Step	Process	Purpose
Resist coating	Spin-on photoresist	Light-sensitive layer
Exposure	UV light through mask	Pattern transfer
Development	Remove exposed resist	Reveal pattern
Etching	Remove unprotected material	Create features

- **Pattern transfer**: From mask to silicon wafer
- **Resolution**: Determines minimum feature size
- **Alignment**: Critical for multiple layer processing
- **UV wavelength**: Shorter wavelength gives better resolution

Mnemonic

"Coat, Expose, Develop, Etch"

Question 4(c) [7 marks]

Explain Regularity, Modularity and Locality.

Solution

Design Principles Table:

Principle	Definition	Benefits	Example
Regularity	Repeated identical structures	Easier design, testing	Memory arrays
Modularity	Hierarchical design blocks	Reusability, maintainability	Standard cells

Locality	Related functions grouped	Reduced interconnect	Functional blocks

Implementation Details:

- **Regularity**: Same cell repeated multiple times reduces design complexity
- **Modularity**: Top-down design with well-defined interfaces
- **Locality**: Minimizes wire delays and routing congestion
- **Design benefits**: Faster design cycle, better testability
- **Manufacturing**: Improved yield through regular patterns

Mnemaid Diagram:

Mermaid Diagram (Code)

```
{Shaded}
{Highlighting}[]
graph LR
    A[System Level] {-{-}{} B[Module Level]}
    B {-{-}{} C[Cell Level]}
    C {-{-}{} D[Device Level]}
    D {-{-}{} E[Regular Structures]}
{Highlighting}
{Shaded}
```

Mnemonic

"Regular Modules with Local Connections"

Question 4(a OR) [3 marks]

Define Design Hierarchy.

Solution

Design Hierarchy Levels:

Level	Description	Components
System	Complete chip functionality	Processors, memories
Module	Major functional blocks	ALU, cache, I/O
Cell	Basic logic elements	Gates, flip-flops

- **Top-down approach**: System broken into smaller modules
- **Abstraction levels**: Each level hides lower level details
- **Interface definition**: Clear boundaries between levels

Mnemonic

"System to Module to Cell"

Question 4(b OR) [4 marks]

Draw and Explain VLSI design flow chart.

Solution

VLSI Design Flow:

Mermaid Diagram (Code)

```
{Shaded}
{Highlighting}[]
graph LR
    A[System Specification] {-{-}{} B[Architectural Design]}
    B {-{-}{} C[Logic Design]}
    C {-{-}{} D[Circuit Design]}
    D {-{-}{} E[Layout Design]}
    E {-{-}{} F[Fabrication]}
    F {-{-}{} G[Testing]}
{Highlighting}
{Shaded}
```

Design Flow Table:

Stage	Input	Output	Tools
Architecture	Specifications	Block diagram	High-level modeling
Logic	Architecture	Gate netlist	HDL synthesis
Circuit	Netlist	Transistor sizing	SPICE simulation
Layout	Circuit	Mask data	Place & route

Mnemonic

"Specify, Architect, Logic, Circuit, Layout, Fabricate, Test"

Question 4(c OR) [7 marks]

Write short note on 'VLSI Fabrication Process'

Solution

Major Fabrication Steps:

Process	Purpose	Result
Oxidation	Grow SiO2 layer	Gate oxide formation
Lithography	Pattern transfer	Define device areas
Etching	Remove unwanted material	Create device structures
Ion Implantation	Add dopants	Create P/N regions
Deposition	Add material layers	Metal interconnects
Diffusion	Spread dopants	Junction formation

Process Flow:

- **Wafer preparation**: Clean silicon substrate
- **Device formation**: Create transistors through multiple steps
- **Interconnect**: Add metal layers for connections
- **Passivation**: Protect completed circuit
- **Testing**: Verify functionality before packaging

Clean Room Requirements:

- **Class 1-10**: Ultra-clean environment needed
- **Temperature control**: Precise process control
- **Chemical purity**: High-grade materials required

Mnemonic

"Oxidize, Pattern, Etch, Implant, Deposit, Diffuse"

Question 5(a) [3 marks]

Compare different styles of Verilog programming in VLSI.

Solution

Verilog Modeling Styles:

Style	Description	Application
Behavioral	Algorithm description	High-level modeling
Dataflow	Boolean expressions	Combinational logic
Structural	Gate-level description	Hardware representation

- **Behavioral**: Uses always blocks, if-else, case statements
- **Dataflow**: Uses assign statements with Boolean operators
- **Structural**: Instantiates gates and modules explicitly

Mnemonic

"Behavior Describes, Dataflow Assigns, Structure Connects"

Question 5(b) [4 marks]

Write Verilog program of NAND gate using behavioral method.

Solution

```
module nand\_gate\_behavioral(
    input wire a, b,
    output reg y
);

always @(a or b) begin
if (a == 1{b1} \&\&

b == 1{b1})

        y = 1{b0};
    else
        y = 1{b1};
end

endmodule
```

Code Explanation:

- **Always block**: Executes when inputs change
- **Sensitivity list**: Contains all input signals
- **Conditional statement**: Implements NAND logic
- **Reg declaration**: Required for procedural assignment

Mnemonic

"Always watch, IF both high THEN low ELSE high"

Question 5(c) [7 marks]

Draw 4X1 multiplexer circuit. Develop Verilog program of the circuit using case statement.

Solution

4X1 Multiplexer Circuit:

```
I0
I1      MUX     Y
I2       4X1
I3
  S1,S0 (Select)
```

Verilog Code:

```
module mux\_4x1\_case(
    input wire [1:0] sel,
    input wire i0, i1, i2, i3,
    output reg y
);

always @(*) begin
    case (sel)
        2{b00}: y = i0;
        2{b01}: y = i1;
        2{b10}: y = i2;
        2{b11}: y = i3;
        default: y = 1{bx};
    endcase
end

endmodule
```

Truth Table:

S1	S0	Output Y
0	**0**	I0
0	**1**	I1
1	**0**	I2
1	**1**	I3

Mnemonic

"Case Selects, Default Protects"

Question 5(a OR) [3 marks]

Define Testbench with example.

Solution

Testbench Definition: Testbench is a Verilog module that provides stimulus to design under test (DUT) and monitors its response.

Example Testbench:

```
module test\_and\_gate;
    reg a, b;
    wire y;

    and\_gate dut(.a(a), .b(b), .y(y));

    initial begin
a = 0;
```

```
b = 0; \#10;

a = 0;

b = 1; \#10;

a = 1;

b = 0; \#10;

a = 1;

b = 1; \#10;

    end
endmodule
```

- **DUT instantiation**: Creates instance of design under test
- **Stimulus generation**: Provides input test vectors
- **No ports**: Testbench is top-level module

Mnemonic

"Test Provides Stimulus, Monitors Response"

Question 5(b OR) [4 marks]

Write Verilog program of Half Adder using Dataflow method.

Solution

```
module half\_adder\_dataflow(
    input wire a, b,
    output wire sum, carry
);

assign sum = a \^{} b;    // XOR for sum
assign carry = a \& b;  // AND for carry

endmodule
```

Logic Implementation:

- **Sum**: XOR operation between inputs
- **Carry**: AND operation between inputs
- **Assign statement**: Continuous assignment for dataflow
- **Boolean operators**: ^ (XOR), & (AND)

Truth Table:

A	B	Sum	Carry
0	**0**	0	0
0	**1**	1	0
1	**0**	1	0
1	**1**	0	1

Mnemonic

"XOR Sums, AND Carries"

Question 5(c OR) [7 marks]

Write function of Encoder. Develop code of 8X3 Encoder using if....else statement.

Solution

Encoder Function: Encoder converts $2^n input lines to output lines. 8X3 encoder converts 8 inputs to 3 – bit binary output.

Priority Table:

Input	Binary Output
I7	111
I6	110
I5	101
I4	100
I3	011
I2	010
I1	001
I0	000

Verilog Code:

```
module encoder\_8x3(
    input wire [7:0] i,
    output reg [2:0] y
);

always @(*) begin
    if (i[7])
        y = 3{b111};
    else if (i[6])
        y = 3{b110};
    else if (i[5])
        y = 3{b101};
    else if (i[4])
        y = 3{b100};
    else if (i[3])
        y = 3{b011};
    else if (i[2])
        y = 3{b010};
    else if (i[1])
        y = 3{b001};
    else if (i[0])
        y = 3{b000};
    else
        y = 3{bxxx};
end

endmodule
```

- **Priority encoding**: Higher index inputs have priority
- **If-else chain**: Implements priority logic
- **Binary encoding**: Converts active input to binary representation

Mnemonic

"Priority from High to Low, Binary Output Flows"